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Bottom-up Patterning Method by using of Microcontact Printing and Atomic Layer Deposition on Silicon

박미현, 장영진, 성명모 국민대학교 화학과

Self-assembled monolayers (SAMs) of alkylsiloxane were patterned by microcontact printing (µCP) on SiO₂, on scales from 0.5 to 100 µm. The patterned SAMs on SiO₂ define and direct the selective deposition of titanium oxide films using atomic layer deposition (ALD) with titanium isopropoxide and water as the precursor. The patterned SAMs and TiO₂ thin films have been investigated by atomic force microscopy (AFM).